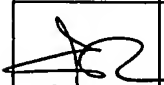

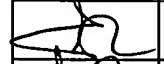
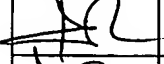


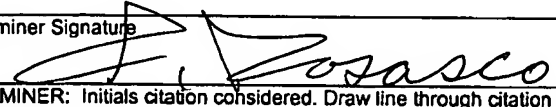


Substitute Form PTO-1449 (Modified)  <b>Information Disclosure Statement by Applicant</b> (Use several sheets if necessary)  (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-870001	Application No. <u>10/665,416</u>
	Applicant Peter Silverman		
	Filing Date September 18, 2003	Group Art Unit	

U.S. Patent Documents							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA						
	AB						
	AC						
	AD						
	AE						

Foreign Patent Documents or Published Foreign Patent Applications								
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AF							
	AG							
	AH							
	AI							
	AJ							

Other Documents (include Author, Title, Date, and Place of Publication)		
Examiner Initial	Desig. ID	Document
	AK	Claude Montcalm, "In situ Characterization of EUV Multiplayer Mirrors Deposited by UHV Magnetron Sputterin", Information Science and Technology, Lawrence Livermore National Laboratory, University of California, Livermore, CA
	AL	Rick Tejada, "EUV Mask Modeling", Computational Mechanics Center, Mechanical Engineering Department, University of Wisconsin-Madison, 03/04/1999
	AM	John E. Bjorkholm, "EUV Lithography-The Successor to Optical Lithography?", Intel Technology Journal Q#98, pages 1-8
	AN	Matthieu F. Bal et al., "the Influence of Multilayers on the Optical Performance of Extreme Ultra Violet Projection Systems", Optics Research Group, Delft University of Technology
	AO	A. Mikkelsen et al., "Mounting Effects on Image Placement Errors", Computational Mechanics Center, Mechanical Engineering Department, University of Wisconsin-Madison
	AP	S. Wolf et al., "Silicon Processing for the VLSI Era", Volume 1; Process Technology, Second Edition, Lattice Press, Sunset Beach, CA, pages 444-450, 468-483, 777, 649-650, and 666

Examiner Signature 	Date Considered <u>4/07</u>
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	